

**Amendments to the Claims:**

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Previously Presented) A stage device, comprising:  
a plurality of movable stages disposed on a certain movement plane so as to be movable independently of each other;  
a first measurement system which measures within a predetermined measurement range a position of one of the plurality of movable stages; and  
a second measurement system which measures an amount of positional deviation of each of the plurality of movable stages from a predetermined reference position within the predetermined measurement range, or a degree of coincidence of each of the plurality of movable stages with respect to the reference position, the second measurement system measuring the amount of positional deviation or the degree of coincidence along a first direction that is perpendicular to the certain movement plane;  
wherein a measurement value obtained with the first measurement system is corrected on the basis of a measurement result of the second measurement system.
2. - 3. (Cancelled)
4. (Previously Presented) An exposure apparatus provided with the stage device according to claim 1, wherein masks on which mutually different patterns are formed are placed on the plurality of movable stages of the stage device, and the patterns of the masks on the plurality of movable stages are alternately transferred onto a substrate while being positioned.
5. (Previously Presented) An exposure apparatus provided with the stage device according to claim 1, wherein a mask is placed on a first movable stage among the plurality of movable stages of the stage device, a characteristic measurement apparatus which measures

characteristics in transfer of a pattern of the mask is placed on a second movable stage of the plurality of movable stages, and the pattern of the mask is transferred onto a substrate.

6. (Previously Presented) An exposure apparatus provided with the stage device according to claim 1, wherein a substrate is placed on each of the plurality of movable stages of the stage device, and the plurality of substrates are alternately exposed with mask patterns while the plurality of movable stages are alternately positioned at an exposure position.

7. (Previously Presented) An exposure apparatus provided with the stage device according to claim 1 and a projection optical system,

wherein a substrate is placed on a first movable stage of the plurality of movable stages of the stage device, a characteristic measurement apparatus which measures imaging characteristics of the projection optical system is placed on a second movable stage of the plurality of movable stages, and the substrate on the first movable stage is exposed with a mask pattern via the projection optical system.

8. (Previously Presented) A positioning method that makes use of the stage device according to claim 1, wherein when one of the plurality of movable stages enters the measurement range of the first measurement system, the amount of positional deviation of the one movable stage from the reference position within the measurement range, or the degree of coincidence of the one movable stage with respect to the reference position, is measured by the second measurement system, and a measurement value obtained with the first measurement system is corrected on the basis of a measurement result of the second measurement system.

9. - 34. (Cancelled)

35. (Previously Presented) A scanning exposure apparatus, comprising:  
a reticle stage which is movable and holds a mask having a pattern;

a first movable stage disposed in a certain movement plane, the first movable stage holding a first substrate on a first holding surface and having a first reflective member on a first side surface of the first movable stage which is perpendicular to the first holding surface;

a second movable stage disposed in the certain movement plane so as to be movable independently from the first movable stage, the second movable stage holding a second substrate on a second holding surface and having a second reflective member on a second side surface of the second movable stage which is perpendicular to the second holding surface;

a scanning system which scans one of the first and second movable stages and the reticle stage along a scanning axis;

a first measurement system which measures within a first measurement range a position of one of the first and second movable stages, the first measurement system being capable of emitting a measurement beam to a mirror of each of the first and second movable stages;

a second measurement system which measures positions of the first and second movable stages within a second measurement range partially overlapping the first measurement range; and

a control system which corrects measurement results of the first and second measurement systems on the basis of the measurement results of the first and second measurement systems.

36. (Previously Presented) The scanning exposure apparatus according to claim 35, wherein the first measurement system emits biaxial beams spaced apart in a direction perpendicular to the certain movement plane.

37. (Previously Presented) The scanning exposure apparatus according to claim 36, wherein the second measurement system emits biaxial beams spaced apart in a direction perpendicular to the certain movement plane.

38. (Previously Presented) The scanning exposure apparatus according to claim 35, wherein the second measurement system emits biaxial beams spaced apart in a direction perpendicular to the certain movement plane.

39. (Previously Presented) The scanning exposure apparatus according to claim 35, wherein the first measurement system emits the measurement beam along the scanning axis.

40. (Previously Presented) The scanning exposure apparatus according to claim 36, wherein the first measurement system emits the biaxial beams along the scanning axis.

41. (Previously Presented) The scanning exposure apparatus according to claim 37, wherein the second measurement system emits the biaxial beams along the scanning axis.

42. (Previously Presented) The scanning exposure apparatus according to claim 38, wherein the second measurement system emits the biaxial beams along the scanning axis.

43. (Previously Presented) A stage device comprising:  
a first movable stage having a first reflective member and a first reference mark;  
a second movable stage having a second reflective member and a second reference mark;  
an interferometer system which cooperates with the first and second reflective members to detect a position of the first and second movable stages alternately;

an optical sensor which detects the first and second reference marks alternately;  
and

a controller which corrects an output of the interferometer system in accordance with a detection result of the optical sensor when the interferometer system detects switching between the position of the first movable stage and the position of the second movable stage.

44. (Previously Presented) The stage device according to claim 43, wherein the first and second movable stages are disposed on a common base.

45. (Previously Presented) The stage device according to claim 43, wherein the first reference mark is located on a first holding surface of the first movable stage and the first reflective member is provided on a first side surface perpendicular to the first holding surface.

46. (Previously Presented) The stage device according to claim 45, wherein the second reference mark is located on a second holding surface of the second movable stage and the second reflective member is provided on a second side surface perpendicular to the second holding surface.

47. (New) The scanning exposure apparatus according to claim 35, wherein the first movable stage and the second movable stage are moved by a planar motor.

48. (New) A scanning exposure apparatus, comprising:  
a first movable stage disposed in a certain movement plane, the first movable stage holding a first substrate on a first holding surface and having a first reflective member on a first side surface of the first movable stage which is perpendicular to the first holding surface;  
a second movable stage disposed in the certain movement plane so as to be movable independently from the first movable stage, the second movable stage holding a second substrate on a second holding surface and having a second reflective member on a

second side surface of the second movable stage which is perpendicular to the second holding surface;

a planar motor which moves the first and second movable stages;

a first measurement system which measures within a first measurement range a position of the first and second movable stages, the first measurement system being capable of emitting a measurement beam to each of the first and second reflective members;

a second measurement system which measures positions of the first and second movable stages within a second measurement range partially overlapping the first measurement range; and

a control system which corrects measurement results of the first and second measurement systems on the basis of the measurement results of the first and second measurement systems.